

Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1. - 11. (Cancelled)

12. (Currently Amended) A scanning exposure method comprising the steps of:
moving a mask having first and second patterns, and a substrate for display panel in synchronization; and
exposing the first and second patterns on the substrate for display panel,
wherein when the first and second patterns are exposed along a synchronous moving direction of the substrate for display panel, a part of the first pattern and a part of the second pattern overlap and are exposed, and a synchronous moving speed of the mask and the substrate for display panel when there is overlapping exposure is set different from a synchronous moving speed of the mask and the substrate for display panel when there is no overlapping exposure; and

wherein a position of a blind plate which sets an illumination region along a direction orthogonal to a scanning direction during a scanning exposure is changed during the scanning exposure so that an overlapping region in which the overlapping exposure is performed extends in a direction that differs from an arrangement direction of the patterns which are arranged parallel to the scanning direction.

13. (Currently Amended) The scanning exposure method according to claim 12, wherein the first pattern and a third pattern adjacent to the first pattern in a direction orthogonal to the synchronous moving direction on the substrate for display panel have pluralities of unit patterns arrayed in different predetermined directions, and when the first and third patterns are exposed, the patterns overlap each other in a direction different from the arraying direction of the unit patterns.

14. (Currently Amended) A scanning exposure method comprising the steps of:
moving a mask having a pattern, and a substrate for display panel with respect
to a region illuminated with an exposing light, in synchronization; and
exposing the pattern on the substrate for display panel,
wherein a size of the illumination region in a direction intersecting with a
synchronous moving direction of the substrate for display panel is synchronously changed
during synchronous movement at the time of exposure in order that a locus of an end of the
illumination region on the substrate for display panel is extended in a direction different from
an arrangement direction of patterns which are arranged parallel to the synchronous moving
direction.

15. (Original) The scanning exposure method according to claim 14, wherein the
size of the illumination region is changed a plurality of times during the synchronous
movement.

16. (Currently Amended) A scanning exposure system which moves a mask having
a pattern, and a substrate for display panel, in synchronization, and exposes the pattern on the
substrate for display panel, comprising:

an illumination region setting device which sets an illumination region of the
mask; and

a changing device which synchronously changes a size of the illumination
region in a direction intersecting with a synchronous moving direction of the substrate for
display panel during synchronous movement at the time of exposure in order that a locus of an
end of the illumination region on the substrate for display panel is extended in a direction
different from an arrangement direction of patterns which are arranged parallel to the
synchronous moving direction.

17. (Currently Amended) A scanning exposure system which moves a mask having a pattern, and a substrate for display panel, in synchronization, and exposes the pattern on the substrate for display panel, comprising:

an illumination region setting device which sets an illumination region of the mask; and

a changing device which changes a size of the illumination region in a direction different from a synchronous moving direction of the substrate for display panel during synchronous movement,

wherein the illumination region setting device includes a pair of blind plates which respectively have openings with a predetermined width in the synchronous moving direction and are movable in a direction that is different from the synchronous moving direction, and

wherein a position of an illumination region along a direction orthogonal to a scanning direction during a scanning exposure is changed during the scanning exposure so that an overlapping region in which an overlapping exposure is performed extends in a direction that differs from an arrangement direction of patterns which are arranged parallel to the scanning direction.

18. (Previously Presented) A scanning exposure system according to claim 17, wherein the illumination region has a pentagonal or hexagonal shape.

19. (Previously Presented) A scanning exposure system according to claim 17, wherein the illumination region setting device provides the illumination region which has triangular ends.

20. (Currently Amended) A scanning exposure system which moves a mask having a pattern, and a substrate for display panel, in synchronization, and exposes the pattern on the substrate for display panel, comprising:

an illumination region setting device which sets an illumination region of the mask; and

a changing device which changes a size of the illumination region in a direction different from a synchronous moving direction of the substrate for display panel during synchronous movement,

wherein ends of the illumination region are inclined relative to an arrangement direction of patterns which are arranged parallel to the synchronous moving direction, and are exposed to an illumination gradient.

21. (Currently Amended) A scanning exposure system which moves a mask having a pattern, and a substrate for display panel, in synchronization, and exposes the pattern on the substrate for display panel, comprising:

an illumination region setting device which sets an illumination region of the mask; and

a changing device which changes a size of the illumination region in a direction different from a synchronous moving direction of the substrate for display panel during synchronous movement and changes a position of the illumination region along a direction orthogonal to a scanning direction during a scanning exposure so that an overlapping region in which an overlapping exposure is performed extends in a direction that differs from an arrangement direction of the patterns which are arranged parallel to the scanning direction,

wherein the illumination region setting device includes at least one blind plate for providing the illumination region with a triangular end and at least one end light-shielding blind plate which covers the triangular end of the at least one illumination region.

22. (Previously Presented) A scanning exposure method according to claim 14, wherein the illumination region has a pentagonal or hexagonal shape.

23. (Currently Amended) A scanning exposure method according to claim 14, wherein the size of the illumination region in a direction intersecting with the synchronous moving direction of the substrate for display panel is continuously changed during the synchronous movement.

24. (Currently Amended) A scanning exposure method according to claim 14, wherein an adjacent pattern is exposed so as to be partially overlapped with the pattern of the mask which was formed on the substrate for display panel.

25. (Currently Amended) A scanning exposure method comprising the steps of:
moving a mask having a pattern, and a substrate for display panel, with respect to a region illuminated with an exposing light, in synchronization; and

exposing the pattern on the substrate for display panel,

wherein a size of the illumination region in a direction intersecting with a synchronous moving direction of the substrate for display panel is synchronously changed during synchronous movement, a position of the illumination region along a direction orthogonal to a scanning direction is changed during a scanning exposure so that an overlapping region in which an overlapping exposure is performed extends in a direction that differs from an arrangement direction of patterns which are arranged parallel to the scanning direction, and wherein an overlapping part which is partially overlapped with the pattern is formed in a zigzag pattern.

26. (Currently Amended) A scanning exposure method according to claim 25, wherein an adjacent pattern, which is adjacent to the pattern in an orthogonal direction to the synchronous moving direction, is exposed so as to be partially overlapped with the pattern of the mask which was formed on the substrate for display panel.

27. (Currently Amended) A scanning exposure method according to claim 25, wherein an adjacent pattern which is adjacent to the pattern in the synchronous moving

direction is exposed so as to be partially overlapped with the pattern of the mask which was formed on the substrate for display panel.

28. (Currently Amended) A scanning exposure method according to claim 26, wherein the adjacent pattern which is adjacent to the pattern in the synchronous moving direction is exposed so as to be partially overlapped with the pattern of the mask which was formed on the substrate for display panel.

29. (Currently Amended) A scanning exposure system according to claim 20, further comprising an alignment member which performs alignment between the mask and the substrate for display panel to partially overlap a part of the pattern of the mask with a part of the pattern which was exposed on the substrate for display panel.

30. (Previously Presented) A scanning exposure system according to claim 29, wherein a synthesized pattern is formed by exposing a plurality of the patterns of the mask in a manner so as to partially overlap the plurality of the patterns.

31. (Currently Amended) A scanning exposure method comprising the steps of:
moving a mask having a pattern, and a substrate for display panel, with respect to an illumination region that is illuminated with an exposing light, in synchronization; and
exposing the pattern on the substrate for display panel,
wherein the illumination region is moved in a direction intersecting with a synchronous moving direction of the substrate for display panel during synchronous movement at the time of exposure so that an overlapping region in which an overlapping exposure is performed extends in a direction that differs from an arrangement direction of patterns which are arranged parallel to the synchronous moving direction.

32. (Currently Amended) A scanning exposure method according to claim 31, wherein a size of the illumination region in the direction intersecting with the synchronous

moving direction of the substrate for display panel is continuously changed during the synchronous movement.

33. (New) A scanning exposure method comprising the steps of:

moving a mask having first and second patterns which have pluralities of unit patterns repeatedly arrayed in a predetermined direction, and a substrate for display panel, in synchronization; and

exposing the first and second patterns on the substrate for display panel,

wherein when the first and second patterns are exposed along a synchronous moving direction of the substrate for display panel, a part of the first pattern and a part of the second pattern overlap and are exposed, and a position or a width of an illumination region along a direction orthogonal to the synchronous moving direction during a scanning exposure, is changed in order that a direction of a region in which the overlapping exposure is performed differs from an arraying direction of the unit patterns which are arranged substantially parallel to the synchronous moving direction.

34. (New) The scanning exposure method according to claim 33, wherein the first pattern and a third pattern adjacent to the first pattern in a direction orthogonal to the synchronous moving direction on the substrate for display panel have pluralities of unit patterns arrayed in different predetermined directions, and when the first and third patterns are exposed, the patterns overlap each other in a direction different from an arraying direction of the unit patterns.

35. (New) The scanning exposure method according to claim 33, wherein a size of the illumination region is changed a plurality of times during the synchronous movement.